

Atomic layer deposition of ZrO₂ thin film using a novel linked cyclopentadienyl-amido Zr precursor

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Fig 1. Comparison of self-saturation

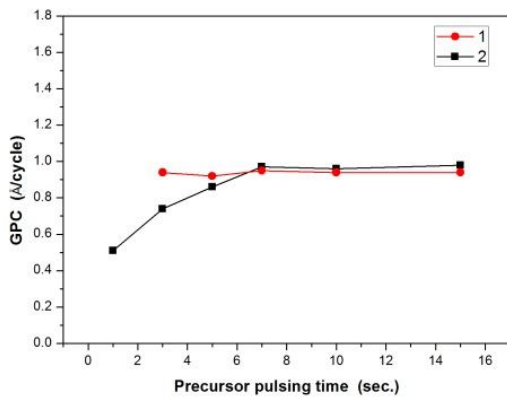


Fig 2. Comparison of ALD window

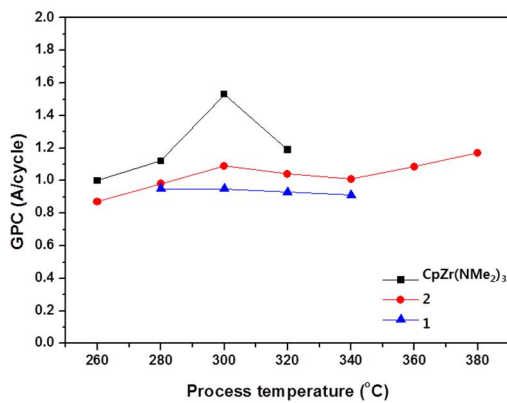


Fig 3. Comparison of Uniformity

